

L Number	Hits	Search Text	DB	Time stamp
-	0	(electrode with formation) and (polymer with insulation) and (coupling with agent) and (catalyst) and (plating electroplating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:23
-	1	(electrode with formation) and (polymer with (dielectric insulative insulation)) and (coupling with agent) and (catalyst) and (plating electroplating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:41
-	36103	(lithography patterning) and ((438/\$) (257/\$)).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:42
-	782	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:42
-	507	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst and treatment	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:42
-	295	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst and treatment) and (palladium pd)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:43
-	241	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst and treatment) and (palladium pd)) and @ad<=20011005	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:53
-	3	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst and treatment) and (palladium pd)) and @ad<=20011005) and (international ibm).as.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:54
-	45357	7and electroplating	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:54
-	28	((lithography patterning) and ((438/\$) (257/\$)).ccls.) and catalyst and treatment) and (palladium pd)) and @ad<=20011005) and electroplating	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/11/29 15:54
-	186	(438/677).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:23
-	2	((438/677).CCLS.) and @ad<=20011005) and ((silane silicon) with coupling)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:26
-	35	((438/677).CCLS.) and @ad<=20011005) and cataly\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:39

-	132065	438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:40
-	208	438/\$ ccls. and ((silicon silane) with coupling with agent)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:45
-	6	(438/\$.ccls. and ((silicon silane) with coupling with agent)) and ((palladium pd) with catalyst)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:51
-	8	("5272111"   "5525204"   "5674787"   "5824599"   "5830563"   "6060176"   "6197688"   "6251781").PN.	USPAT	2002/12/13 11:44
-	91	216/\$.ccls. and ((silicon silane) with coupling with agent)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:50
-	26	(438/\$.ccls. and ((silicon silane) with coupling with agent)) and (solution with cataly\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:47
-	9	(438/\$ ccls. and ((silicon silane) with coupling with agent)) and ((palladium pd) with cataly\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:51
-	4	(216/\$.ccls. and ((silicon silane) with coupling with agent)) and ((palladium pd) with cataly\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:51
-	171	((438/677).CCLS.) and @ad<=20011005	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/13 11:52
-	5	5604153.URPN.	USPAT	2002/12/14 11:17
-	7	("4460618"   "5091210"   "5179042"   "5180687"   "5196372"   "5208187"   "5217756").PN.	USPAT	2002/12/14 11:18
-	5	5569628.URPN.	USPAT	2002/12/14 11:45
-	12	("4592800"   "5091103"   "5312776"   "5466389"   "5514478"   "5538921"   "5569628"   "5648324"   "5665688"   "5780406"   "5798323"   "5817610").PN.	USPAT	2002/12/14 11:47
-	1	"5312776".PN.	USPAT	2002/12/14 11:47
-	13	treat\$3 with (insulation insulative dielectric) and "coupling agent" and (cataly\$3 with solution)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:08
-	2	("5569628").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:45
-	2391	((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:46

-	163	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and (silane silicon coupl\$3) with (agent solution))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:59
-	25	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and (silane silicon coupl\$3) with (agent solution)) and cataly\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:57
-	0	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and (silane silicon coupl\$3) with (agent solution)) and selective with deposition with catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:58
-	0	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and (silane silicon coupl\$3) with (agent solution)) and selective with deposition	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:58
-	0	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and selective with deposition with catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 12:58
-	6	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and (silane silicon coupl\$3) with (agent solution)) and "coupling agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:29
-	8	("5272111"   "5525204"   "5674787"   "5824599"   "5830563"   "6060176"   "6197688"   "6251781").PN.	USPAT	2002/12/14 13:20
-	18	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and catalyst with solution and palladium	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:30
-	19	((((438/627) or (438/628) or (438/641) or (438/643) or (438/644) or (438/678) or (438/800) or (438/942)).CCLS.) and catalyst with solution and (palladium pd)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:35
-	559	((((438/\$) (257/\$)).ccls.) and "coupling agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:37
-	7	((((438/\$) (257/\$)).ccls.) and "coupling agent") and catalyst with treatment	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:47
-	6	((("6495005") or ("5925259") or ("5817242") or ("6391691")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:51
-	710	((andry flake michel tsujimura).inv.) and ((ibm international).as.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:54
-	0	((((andry flake michel tsujimura).inv.) and ((ibm international).as.)) and catalyst and "coupling agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:53

-	6	((andry flake michel tsujimura).inv.) and ((ibm international).as.)) and catalyst and "coupling agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:54
-	175	((andry flake michel tsujimura).inv.) and ((ibm).as.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:56
-	0	((andry flake michel tsujimura).inv.) and ((ibm).as.)) and "coupling agent"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:55
-	1	((andry flake michel tsujimura).inv.) and ((ibm).as.)) and catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:55
-	671	((andry flake michel tsujimura).inv.) and ((ibm (international with machines).as.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 13:57
-	15	((andry flake michel tsujimura).inv.) and ((ibm (international with machines).as.))) and catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:05
-	251200	((438/\$) (257/\$).ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:07
-	268205	((438/\$) (257/\$)).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:07
-	88	((438/\$) (257/\$)).ccls.) and insulation with functional	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:08
-	20	((438/\$) (257/\$)).ccls.) and insulation with functional) and coupling	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:10
-	3	((438/\$) (257/\$)).ccls.) and insulation with functional) and catalyst	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 14:12
-	1666	"coupling agent" with "catalyst"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 17:16
-	31	("coupling agent" with "catalyst") and "conductive layer"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/12/14 17:16
-	9	("4548867"   "4946903"   "5051312"   "5079600"   "5206309"   "5266309"   "5342737"   "5389496"   "5500315").PN.	USPAT	2002/12/14 17:22

-	5	5500315.URPN.	USPAT	2002/12/14 17:25
-	215061	"427"	USPAT;	2002/12/14 17:42
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	3179	((427/98) or (427/301) or (427/304) or (427/305) or (427/306)).CCLS.	USPAT;	2002/12/14 17:42
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	46	((427/98) or (427/301) or (427/304) or (427/305) or (427/306)).CCLS.) and "coupling agent" and "catalyst"	USPAT;	2002/12/14 17:43
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	30	((427/98) or (427/301) or (427/304) or (427/305) or (427/306)).CCLS.) and "coupling agent" and "catalyst") and (electroplating electroless)	USPAT;	2002/12/14 17:44
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	95	5079600.URPN.	USPAT	2002/12/14 17:55